



Attorney Docket No. 253/006 CIP 2

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Jung-ho LEE, et al.

Art Unit: 2818

Serial No. 10/779,733

Examiner: Renee R. Berry

Filed: February 18, 2004

Confirmation No. 2084

For: METHOD OF FORMING SILICON OXIDE LAYER
IN SEMICONDUCTOR MANUFACTURING
PROCESS

AMENDMENT UNDER 37 C.F.R. §1.312

Mail Stop Issue Fee
Commissioner for Patents
P.O. Box 1450
Alexandria, Va. 22313-1450

Sir:

INTRODUCTORY COMMENTS

In connection with the payment of the issue fee filed concurrently herewith,
applicants respectfully submit the following amendments and remarks:

Amendments to the Drawings begin on page 2 of this paper.

Remarks begin on page 3 of this paper.